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Qur Docket	No: 42390P10058		Patent	
2 13	IN THE UNITED STATES PATE	NT AND TRAD	EMARK OFFICE	(m) [2
In te Applica	ation of:			, ,
	Han-Ming Wu et al.	Examiner:	Nguyen, Hung	,
Serial No:	09/752,938	Art Unit:	2851	,
Filed:	December 29, 2000			•
Enclosi	g Gas from a Photolithography) ure Between a Mask Protective) and a Pattern Mask)			
	RESPONSE TO C e Amendment mmissioner for Patents	OFFICE ACTIO	<u>N</u>	
Washington,				
Sir:				
In re	sponse to the Office Action mailed	February 25, 2	002 the Applicants res	pectfully
request the E	Examiner to enter the following amer	ndments and to c	onsider the following re	marke
				marks.
	FIRST CLASS CERTIF	FICATE OF MAILI	<u>NG</u>	
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Docket No.: 42390P10058 Application No.: 09/752,938 March 8, 2002

Date